

# Enhancement of stability in *n*-channel OFETs by modulating polymeric dielectric

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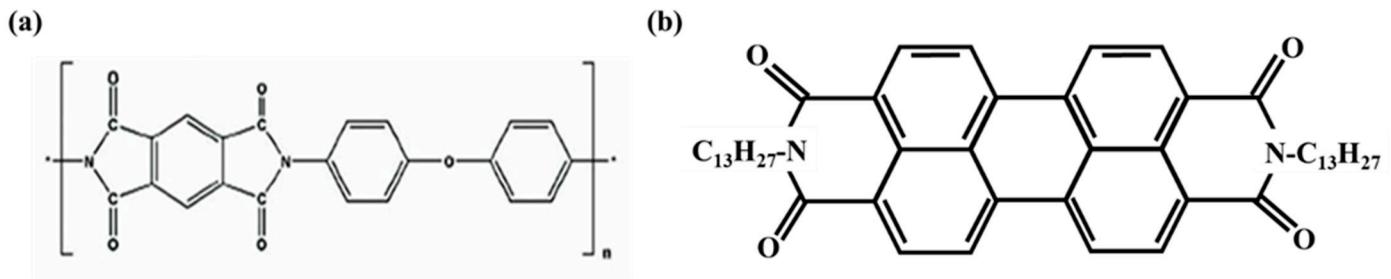
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**Table S1.** Performance criteria of OFETs with different dielectrics (averaging by 10 devices).

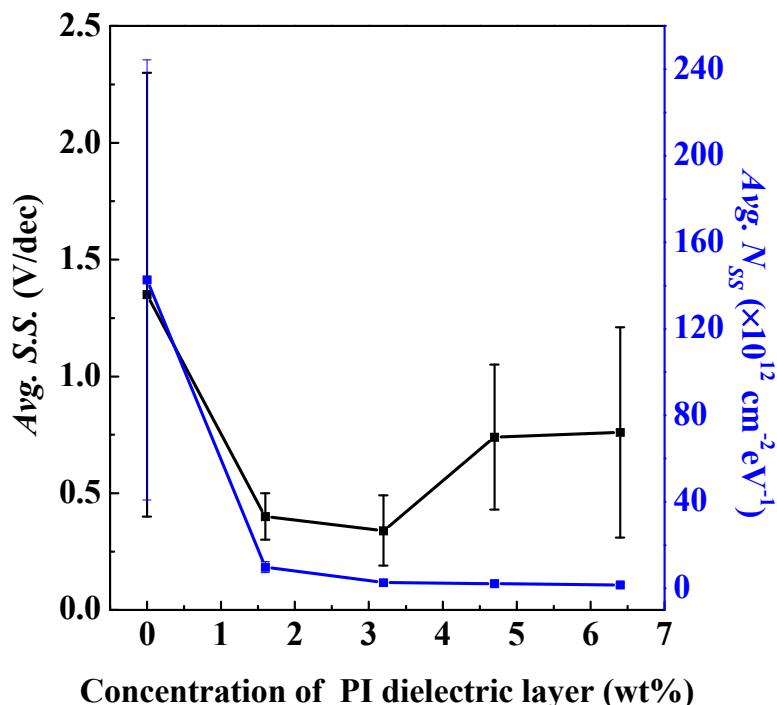
Dielectric of OFETs	$V_{th}$ (V)	$I_{On}/I_{Off}$ Ratio	S.S. (V/dec)	Mobility (cm <sup>2</sup> /Vs)
PI (6.4 wt%) /AlO <sub>x</sub>	-0.83 ± 0.41	(3.8 ± 3.4) × 10 <sup>3</sup>	0.76 ± 0.45	(2.5 ± 1.7) × 10 <sup>-3</sup>
PI (4.7 wt%) /AlO <sub>x</sub>	-0.26 ± 0.16	(1.5 ± 1.2) × 10 <sup>4</sup>	0.74 ± 0.31	(2.3 ± 1.4) × 10 <sup>-3</sup>
PI (3.2 wt%) /AlO <sub>x</sub>	0.16 ± 0.12	(2.5 ± 2.4) × 10 <sup>4</sup>	0.34 ± 0.15	(1.0 ± 0.7) × 10 <sup>-2</sup>
PI (1.6 wt%) /AlO <sub>x</sub>	0.13 ± 0.09	(1.3 ± 1.0) × 10 <sup>4</sup>	0.40 ± 0.10	(1.6 ± 1.1) × 10 <sup>-2</sup>
AlO <sub>x</sub>	0.15 ± 0.04	(1.9 ± 1.7) × 10 <sup>2</sup>	1.35 ± 0.95	(1.5 ± 0.6) × 10 <sup>-4</sup>

**Table S2.** Comparison of mobilities between different references and this work.

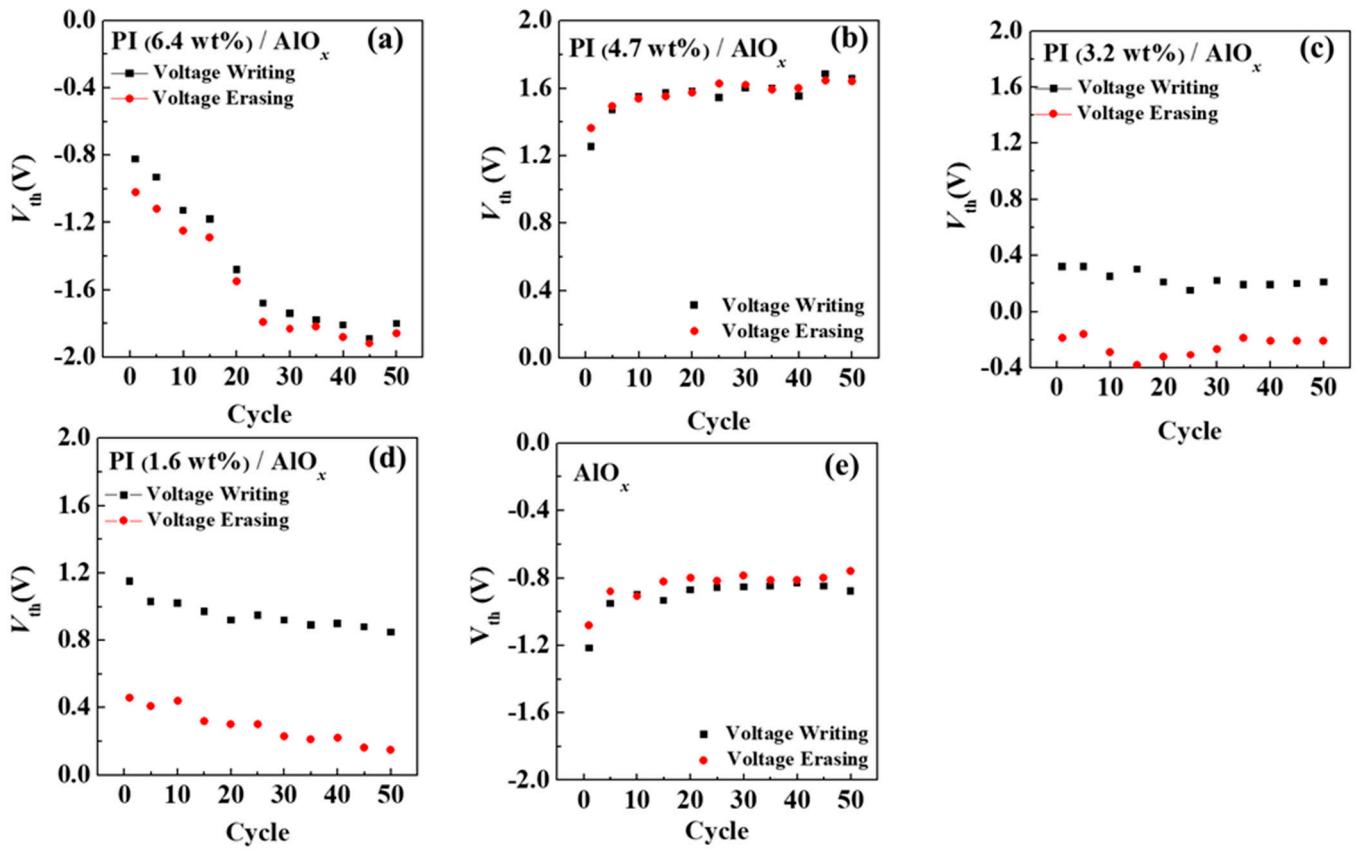
Semiconductor	Mobility (cm <sup>2</sup> /Vs)	Ref.
[5] phenacene	1.5 × 10 <sup>-3</sup>	35
P(NDI2OD-T <sub>2</sub> )	3.4 × 10 <sup>-3</sup>	36
PTCDI-C <sub>13</sub>	2.3 × 10 <sup>-2</sup>	37
C <sub>3</sub> F <sub>7</sub> CH <sub>2</sub> -PTCDI-(CN) <sub>2</sub>	4.0 × 10 <sup>-2</sup>	38
PTCDI-C <sub>13</sub>	1.4 × 10 <sup>-2</sup>	39
PTCDI-C <sub>13</sub>	1.6 × 10 <sup>-2</sup>	40
PTCDI-C <sub>13</sub>	2.7 × 10 <sup>-3</sup>	41
4Cl-PDI-3EG	8.0 × 10 <sup>-4</sup>	42
PTCDI-C <sub>13</sub>	1.5 × 10 <sup>-2</sup>	This work



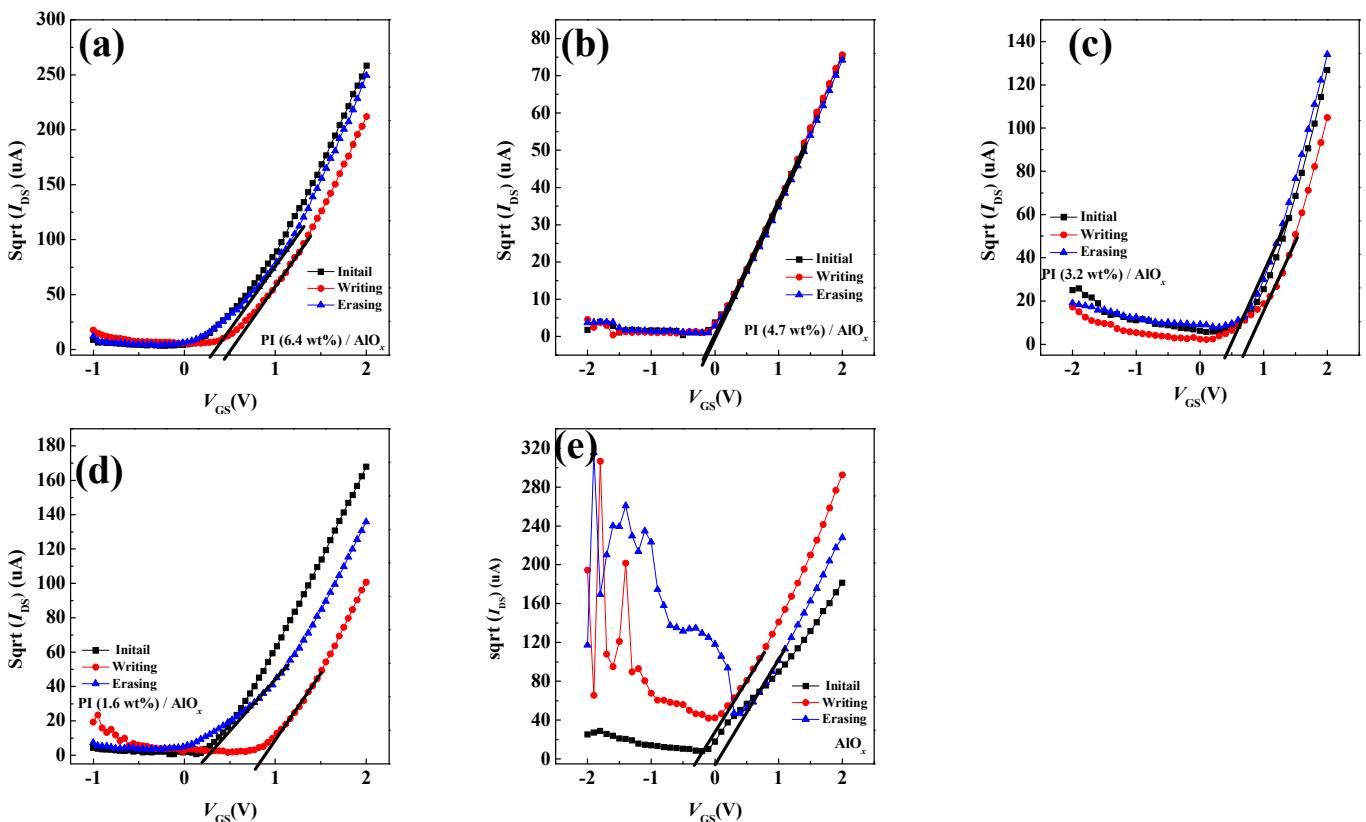
**Figure S1.** The chemical structures of (a) polymer dielectric material PI, and (b) organic semiconductor material PTCDI-C<sub>13</sub>.



**Figure S2.** The relationship between the S.S. and N<sub>ss</sub> of the OFETs versus the different solid contents of the PI layer, in which 10 devices are used for averaging.



**Figure S3.** The  $V_{th}$  variation chart of writing-erasing for organic memory devices fabricated by using PI films with different solid contents (a) 6.4 wt%, (b) 4.7 wt%, (c) 3.2 wt%, (d) 1.6 wt%, and (e) native  $\text{AlO}_x$ .



**Figure S4.** The memory characteristics chart of writing-erasing behaviors for organic memory devices fabricated by using PI films with different solid contents (a) 6.4 wt%, (b) 4.7 wt%, (c) 3.2 wt%, (d) 1.6 wt%,

and (e) native AlO<sub>x</sub>.